## Delocalized Nature of the $E'_{\delta}$ Center in Amorphous Silicon Dioxide

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We report an experimental study by electron paramagnetic resonance (EPR) of  $E'_{\delta}$  point defect induced by  $\gamma$ -ray irradiation in amorphous  $\mathrm{SiO}_2$ . We obtained an estimation of the intensity of the 10 mT doublet characterizing the EPR spectrum of such a defect arising from hyperfine interaction of the unpaired electron with a  $^{29}\mathrm{Si}$  (I=1/2) nucleus. Moreover, determining the intensity ratio between this hyperfine doublet and the main resonance line of  $E'_{\delta}$  center, we pointed out that the unpaired electron wave function of this center is actually delocalized over four nearly equivalent silicon atoms.

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One of the most important reasons for interest in amorphous silicon dioxide  $(a\text{-SiO}_2)$  is related to the fact that  $a\text{-SiO}_2$  is found as a gate in almost the totality of the modern MOS (metal-oxide-semiconductor) devices [1–3]. However, by exposing these devices to irradiation, a large concentration of point defects is generated in the oxide layer. Since some of these point defects act as charge traps, the devices undergo a sensible threshold voltage shift that definitively determines their failure [3,4]. The defects prevalently responsible for this effect are the paramagnetic  $E'_{\gamma}$  and  $E'_{\delta}$  centers.

The  $E'_{\gamma}$  center has been widely studied and its most accepted model consists of a positively charged puckered oxygen vacancy:  $O = Si^{\bullet} + Si = O$  (where = represents the bonds to three oxygen atoms,  $\bullet$  represents an unpaired electron, and + is a trapped hole) [1,2,5,6], the unpaired electron being localized in a  $sp^3$  hybrid orbital of one silicon atom. This structural model followed the definitive attribution to the same defect of a doublet of electron paramagnetic resonance (EPR) lines split by  $\sim$ 42 mT, arising from the hyperfine interaction of the unpaired electron with a  $^{29}Si$  nucleus (4.7% natural abundant isotope with nuclear spin I = 1/2) [5]. Following the above reported microscopic model, the  $E'_{\gamma}$  center is considered as the equivalent in a-SiO<sub>2</sub> of the  $E'_1$  center of quartz [5–11].

The  $E_\delta'$  center was observed in x-ray and  $\gamma$ -ray irradiated bulk SiO<sub>2</sub> [12–14], in thermally grown thin SiO<sub>2</sub> films upon annealing [15–18], and in buried oxide layers obtained by oxygen implantation (SIMOX) [19,20]. The principal EPR characteristics of this center are a main resonance line showing nearly isotropic g tensor ( $g \sim 2.002$ ) and a pair of lines with a separation of  $\sim 10$  mT, supposed to arise from hyperfine interaction of the unpaired electron with a  $^{29}$ Si nucleus (I = 1/2) [12,14]. The hole-trap nature of the  $E_\delta'$  center was also verified [20,21]. An intriguing feature regarding the  $E_\delta'$  center is that in the same materials in which this center is induced, another characteristic EPR signal with  $g \sim 4$  is also found, attributed to a point defect in a triplet state (pair of coupled electrons with total spin S = 1) [12–14].

The  $E'_{\delta}$  center microscopic structure is still not univocally determined. Until now, four distinct models were

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proposed for this center. The nearly isotropic g tensor, together with the fact that the <sup>29</sup>Si hyperfine splitting (~10 mT) is ~4 times smaller than that of  $E'_{\nu}$  center (~42 mT), have lead Griscom et al. [12] to introduce a model in which the unpaired electron is delocalized over four mutually orthogonal Si  $sp^3$  orbitals, each one similar to the one involved in the  $E'_{\nu}$  center. Since the concentration of  $E'_{\delta}$  center induced by irradiation was found to correlate with the chlorine content of the investigated samples, a model consisting of an electron delocalized over a [SiO<sub>4</sub>]<sup>4+</sup> vacancy decorated by three Cl<sup>-</sup> ions was proposed (4-Si Cl-containing model). However, as the same authors pointed out, the absence of the EPR lines due to the hyperfine interaction of the unpaired electron with the I = 3/2 nuclei of <sup>35</sup>Cl and <sup>37</sup>Cl (with 75.4% and 24.6% natural abundance, respectively) represented a serious difficulty for the reliability of this model. Successively, Tohmon *et al.* [13] have pointed out that  $E'_{\delta}$  centers can be induced in an equivalent way in Cl- or F-doped SiO<sub>2</sub>. However, the authors have evidenced that a necessary condition for the formation of this defect is the oxygen deficiency of the material, revealing that the precursor of  $E'_{\delta}$  center is actually an oxygen deficient defect. So, a microscopic model was proposed consisting of an ionized single oxygen vacancy with the unpaired electron shared nearly equally by the two Si atoms (2-Si model). Vanheusden *et al.* [19] have reported that  $E'_{\delta}$  centers, together with  $E'_{\gamma}$  centers, can be induced in Cl and F free SIMOX materials, clarifying definitively that these impurities are not directly involved in  $E'_{\delta}$  centers. Moreover, an important difference regarding the depth profiles of  $E'_{\gamma}$  and  $E'_{\delta}$  centers was pointed out. The  $E'_{\delta}$  centers, in fact, are induced in the oxide layer nearer to the interface with the Si substrate than the  $E'_{\gamma}$  centers [19]. Based on this experimental evidence a microscopic structure was proposed for  $E'_{\delta}$  consisting of an unpaired electron delocalized over four Si atoms coordinated to a fifth Si atom disposed at the center of a tetrahedron (5-Si cluster model).

In order to discern between the various models of  $E'_{\delta}$ , a relevant role is played by the hyperfine structure. In fact, the ratio  $\zeta$  between its intensity and that of the main resonance line is expected to have the value

$$\zeta = \frac{\text{hyperfine doublet EPR intensity}}{\text{main resonance EPR intensity}}$$
$$= 0.047n(1-0.047)^{(n-1)},$$

where 0.047 is the natural abundance of  $^{29}$ Si nuclei and nindicates that the unpaired electron wave function is delocalized over n Si atoms.  $\zeta$  increases on increasing nbecause the hyperfine intensity is related to the number of equivalent Si sites of the defect in which the <sup>29</sup>Si nucleus can be found. Zhang et al. [14] reported an experimental estimation of  $\zeta$ . However, in their samples the concentration of  $E'_{\delta}$  centers was low and consequently the only way to detect the 10 mT doublet was to use the high-power second-harmonic measurements. Nevertheless, by this experimental technique a quantitative estimation of the concentration of centers cannot be obtained. So, only postulating a strict similarity between the properties of  $E'_{\gamma}$  and  $E'_{\delta}$  centers' second-harmonic EPR signals, the authors could estimate  $\zeta \approx 0.175$ , compatible with the value of 0.163 expected for n = 4. This outcome was the basis for the introduction of a microscopic model for the  $E'_{\delta}$  consisting of a  $[SiO_4]^+$  vacancy (4-Si model).

In this Letter we report the first direct experimental estimation of the concentration of defects responsible for the 10 mT hyperfine doublet by ordinary EPR measurements (first-harmonic unsaturated mode). This estimation has permitted us to evaluate the ratio  $\zeta$  and to shed new light on the microscopic structure of  $E'_{\delta}$  center.

The material considered in this work is a high purity natural bulk  $a\text{-SiO}_2$  type I, Pursil 453 [22]. An optical absorption band at  $\sim$ 7.6 eV of amplitude larger than 100 cm<sup>-1</sup> and an absorption band at  $\sim$ 5.0 eV of amplitude  $\sim$ 0.4 cm<sup>-1</sup> characterize the material as an oxygen deficient silicon dioxide. The Cl and F content of Pursil 453 is lower than  $\sim$ 7 × 10<sup>15</sup> cm<sup>-3</sup> [22]. Samples with size 5 × 5 × 1 mm<sup>3</sup> were exposed to different  $\gamma$ -ray irradiation doses (at room temperature) in the range from 5 to  $10^4$  kGy at a rate  $\sim$ 7 kGy/h.

EPR measurements were carried out at room temperature and at frequency  $\nu \approx 9.8$  GHz with a Bruker EMX spectrometer working in the first-harmonic unsaturated mode and in high-power second-harmonic mode. In particular, the latter method was used to detect the 10 mT hyperfine doublet when a larger sensitivity was required. All the spectra were acquired with a magnetic-field modulation frequency of 100 kHz. Concentration of defects was determined, with an accuracy of 10%, comparing the double integral of the first-harmonic EPR spectrum with that of a reference sample. For the reference sample, the defect concentration was evaluated, with absolute accuracy of 20%, using the instantaneous diffusion method in spinecho decay measurements carried out in a pulsed spec-

trometer [23]. The intensity of the second-harmonic EPR signal was estimated by simple integration of the spectra.

In Fig. 1 the EPR spectrum obtained in correspondence to  $g \sim 2$  for a sample irradiated at  $10^3$  kGy is reported. As already pointed out [12], this spectrum arises from the partial superposition of two distinct resonance lines ascribed to  $E'_{\gamma}$  and  $E'_{\delta}$  centers, as indicated by arrows in Fig. 1. The EPR signal of the triplet center was also detected in correspondence to  $g \sim 4$  for the same sample. From the analysis of similar spectra obtained for all the other irradiated samples, the dose dependence of the concentration of these three different defects was obtained.  $E'_{\delta}$ and triplet centers were found to grow for doses below  $\sim 10^3$  kGy; at variance, for  $E'_{\gamma}$  centers no saturation of concentration was reached up to the highest investigated doses. Second-harmonic measurements were also performed to detect the 10 mT hyperfine doublet, but due to the presence of other overlapping signals, a quantitative analysis was prevented.

To isolate the 10 mT doublet a sample irradiated at  $\sim 10^3$  kGy was subjected to 25 min isochronal thermal treatments in the range of temperature from 330 to 800 K with steps of 10 K. Each temperature of the treatment was stabilized within 3 K. The concentration of  $E'_{\delta}$  was monitored during the thermal treatment and is reported in Fig. 2(a). The  $E'_{\delta}$  center begins to anneal in the temperature range 400-480 K and after that, for  $T \sim 500$  K, a production mechanism is activated and the concentration of defects increases. A maximum concentration ~4 times greater than the initial value is reached after the thermal treatment at  $\sim$ 580 K, while for higher temperature the  $E_{s}'$ centers anneal. A growth of concentration was also found for  $E'_{\gamma}$  centers but for these defects the production mechanism was found to start at ~540 K. An analogous growth of concentration is typically observed in irradiated quartz [10], in which, for  $T \sim 500$  K, the  $E'_1$  center concentration grows in correspondence to the annealing of [AlO<sub>4</sub>]<sup>0</sup> hole centers. In the SiO<sub>2</sub> sample considered here, a concentration of  $\sim 10^{17}$  spins/cm<sup>3</sup> of [AlO<sub>4</sub>]<sup>0</sup> centers was estimated

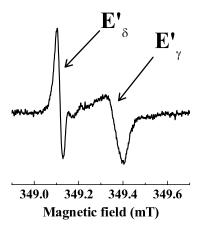
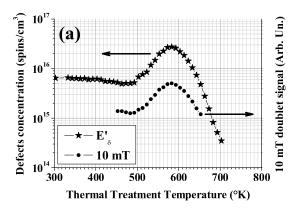


FIG. 1. First-harmonic unsaturated mode EPR spectrum showing partially superimposed  $E'_{\gamma}$  and  $E'_{\delta}$  resonance lines.



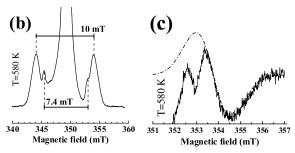


FIG. 2. Pursil 453 sample irradiated at a  $\gamma$ -ray irradiation dose of  $\sim 10^3$  kGy: (a)  $E'_{\delta}$  center concentration (left vertical scale) and 10 mT doublet intensity (right vertical scale) as a function of the thermal treatment temperature. (b) High-power second-harmonic EPR spectrum and (c) first-harmonic unsaturated EPR spectrum (noisy line), after the thermal treatment at  $\sim 580$  K. In (c) superimposed to the spectrum is a derivative Gaussian line shape (broken line).

by EPR measurements before heating. Furthermore, these impurity centers were found to anneal out in the same temperature range in which the growth of  $E'_{\delta}$  and  $E'_{\gamma}$  centers occur. So, in analogy with the process proposed in quartz [10], we suggest that in Pursil 453 a hole transfer could occur from [AlO<sub>4</sub>]<sup>0</sup> centers to the sites precursors of  $E'_{\delta}$  and  $E'_{\gamma}$ .

For the temperature of the treatment in the range of  $450-650~\rm K$  the 10 mT doublet can be isolated in the second-harmonic spectra, as shown in Fig. 2(b) for  $T\sim580~\rm K$ . The 7.4 mT doublet characteristic of hydrogenated point defect is also distinguishable in this spectrum [24]. Performing a fit procedure with Gaussian line shapes for 10 and 7.4 mT doublets, an estimation of the second-harmonic intensity of the 10 mT pair was obtained. In Fig. 2(a) the intensity of the 10 mT doublet as a function of the temperature of the treatment is shown. From this figure it is evident that the 10 mT doublet temperature dependence is strictly correlated to that of the  $E_\delta'$  center, corroborating the assignment of the doublet to the hyperfine structure of  $E_\delta'$  center.

Since the concentration cannot be evaluated by second-harmonic measurements, first-harmonic unsaturated spectra were also performed for the 10 mT doublet. In Fig. 2(c) (noisy line) the spectrum for the right component of the

doublet is reported for  $T \sim 580$  K. We note that partially superimposed to the signal of the 10 mT line, on the low field side of the spectrum, are some structures that vanish for magnetic field higher than ~353.5 mT. Since from second-harmonic measurements we verified that each line of the 10 mT doublet is well described by a Gaussian profile, to evaluate the intensity of the 10 mT signal we have superimposed a Gaussian derivative line to the experimental spectrum [broken line in Fig. 2(c)]. From this intensity, the concentration of centers responsible for the 10 mT doublet was determined. This analysis was also repeated after the thermal treatments at T = 600, 610, and 620 K, and the obtained concentration is reported in Fig. 3 as a function of  $E'_{\delta}$  center concentration. These data points show a linear correlation, the slope being the ratio  $\zeta$ . Performing a best fit procedure, the value  $\zeta = 0.16 \pm 0.02$ was obtained. This intensity ratio is consistent with the value  $\zeta = 0.163$  expected for n = 4, unambiguously indicating that the unpaired electron wave function of the  $E'_{\delta}$ center is actually delocalized over four nearly equivalent silicon atoms.

Our result definitively rules out that the  $E'_{\delta}$  center could consist of a ionized single oxygen vacancy. This structural model has been supported by several computational works [25–32] based on a predicted <sup>29</sup>Si hyperfine doublet compatible with that of the  $E'_{\delta}$  center [25,26,30–32]. However, the expected value of  $\zeta$  for this defect is 0.090 in disagreement, beyond any experimental uncertainty, with the estimation reported here. So, if this defect really exists in  $a\text{-SiO}_2$ , it should be well distinguishable from the  $E'_{\delta}$  center. Furthermore, we note that, owing to its axial symmetry, the EPR signal of the ionized single oxygen vacancy should be different from that of the  $E'_{\delta}$  center and more similar to that of the  $E'_{\gamma}$ .

The models compatible with our data are the 4-Si (Zhang *et al.* [14]) and the 5-Si cluster (Vanheusden *et al.* [19]). In both models [14,19] the  $E'_{\delta}$  center consists

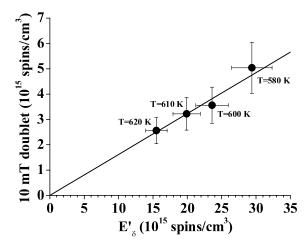


FIG. 3. Concentration of defects responsible for the 10 mT doublet as a function of  $E_{\delta}'$  concentration. The line is obtained by linear fit to the data.

of an unpaired electron delocalized in a wave function composed by the four  $sp^3$  hybrid orbitals of the nearby Si atoms. The defect could originate from a radiation induced ionization of a pair of nearby oxygen vacancies (O = Si–Si = O) [14] or of a 5-Si cluster [19]. Irradiation removes an electron from one of the Si-Si bonds, and after a dynamical relaxation, the remaining unpaired electron becomes delocalized over four symmetrically disposed silicon atoms. In this scheme and under the hypothesis of similar precursors for  $E'_{\delta}$  and triplet centers [12–14] we suggest that the latter defect could be generated by double ionization of the  $E'_{\delta}$  center precursor.

In conclusion, our data support a structure of  $E'_{\delta}$  centers in which the unpaired electron is delocalized over four  $sp^3$ hybrid orbitals of nearby Si atoms. We stress that this structure agrees with the main experimental evidences of this defect as described in the following. The g tensor is nearly isotropic as expected for delocalized highly symmetric electronic wave functions. The hyperfine splitting of the  $E'_{\delta}$  center is  $\sim$ 4 times smaller than that of the  $E'_{\gamma}$  center  $(10 \text{ mT} \approx 1/4 \times 42 \text{ mT})$  due to delocalization of the electron over four orbitals similar to the one of the  $E'_{\gamma}$  center. The intensity ratio  $\zeta$  between the 10 mT hyperfine doublet and the  $E_{\delta}'$  main EPR line is  $\zeta \sim 0.16$ . This is the consequence of the existence of four nearly equivalent sites of the defect in which the <sup>29</sup>Si can be localized. Finally, the different depth profiles of the  $E'_{\delta}$  and  $E'_{\gamma}$  centers observed in SIMOX samples [19] are a direct consequence of the higher oxygen deficiency needed for the formation of the precursors of  $E'_{\delta}$  (two close oxygen vacancies or small Si cluster) with respect to  $E'_{\gamma}$  centers (single oxygen vacancy). The  $E_{\delta}'$  and  $E_{\gamma}'$  centers are then useful probes to characterize the degree of oxygen deficiency in Si/SiO<sub>2</sub> interfaces.

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